Thermal and Plasma CVD of **Nanostructures**

Editor:

M. K. Sunkara University of Louisville Louisville, Kentucky, USA

Sponsoring Division:



Dielectric Science & Technology



The Electrochemical Society

65 South Main Street, Building D Pennington, NJ 08534-2839, USA

www.electrochem.org

Aestransactions ™

Vol. 13 No. 9

Copyright 2008 by The Electrochemical Society. All rights reserved.

This book has been registered with Copyright Clearance Center. For further information, please contact the Copyright Clearance Center, Salem, Massachusetts.

Published by:

The Electrochemical Society 65 South Main Street Pennington, New Jersey 08534-2839, USA

> Telephone 609.737.1902 Fax 609.737.2743 e-mail: ecs@electrochem.org Web: www.electrochem.org

ISSN 1938-6737 (online) ISSN 1938-5862 (print)

ISBN 978-1-56677-666-0 (PDF) ISBN 978-1-60768-018-5 (Softcover)

Printed in the United States of America.

ECS Transactions, Volume 13, Issue 9 Thermal and Plasma CVD of Nanostructures

Table of Contents

Preface	iii
Analysis of Silicon Dioxde Nanowires Synthesized via Rapid Thermal Annealing of	1
Pt-coated Si Substrates Y. Lai, J. Wang and S. Liou	
Modeling of Thermodynamic and Transport Phenomena in CVD Processes for Nano-Scale Applications R. Nagarajan, P. Gorai and N. Chawla	7
Author Index	19